



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : PATENT APPLICATION
Lebouitz et al. :
Serial No. 09/839,763 : **APPARATUS FOR ETCHING
SEMICONDUCTOR SAMPLES AND A
SOURCE FOR PROVIDING A GAS BY
SUBLIMATION THERETO**
Filed April 20, 2001 :

INFORMATION DISCLOSURE STATEMENT

Pittsburgh, Pennsylvania 15222

May 31, 2001

Assistant Commissioner for Patents

Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.51, 1.56, 1.97 and 1.98, a copy of the art identified on attached form PTO-1449 is enclosed herewith as a citation in connection with the captioned application. The applicants hereby request the Examiner to review and make an independent evaluation of the art. A copy of each reference is provided.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231 on:

May 31, 2001
Date of Deposit

Philip E. Levy
Name of Person Signing


Signature

Gelernt et al., U.S. Patent No. 4,415,402

Gifford et al., U.S. Patent No. 5,200,023

Pister, U.S. Patent No. 5,726,480

Coronel et al., U.S. Patent No. 5,807,761

Guinn et al, U.S. Patent No. 5,877,032

Cadet et al., U.S. Patent No. 5,877,407

Turner et al., U.S. Patent No. 5,939,886

McQuarrie et al., European Patent No. EP 0 878 824 A2

Kobayashi, Japanese Patent No. 02187025

Choi, et al., Japanese Patent No. 11145067

Cho et al., Japanese Patent No. 11204509

Baker et al., Japanese Patent No. 11265878

H.F. Winters and J.W. Coburn, "Etching of Silicon with XeF₂ Vapor,"
App. Phy. Lett., Vol. 34, No. 1, pp. 70-73, Jan. 1979

S.J. Sherman, W.K. Tsang, T.A. Core, D.E. Quinn, "A Low Cost Monolithic Accelerometer," 1992 Symposium on VLSI Circuits, Digest of Technical Papers, Seattle, WA, USA, pp. 34-35, June 4-6, 1992.

P.B. Chu, J.T. Chen, R. Yeh, G. Lin, J.C.P. Huang, B.A. Warneke and K.S.J. Pister, *Transducers* 1997, Chicago, IL, pp. 16-19, June 1997

For Japanese Patent Nos. 02187025, 11145067, 11204509 and 11265878, which are not in English, a statement of the relevance thereof has been provided in the "Background" portion of the present application at pages 2 and 6. Also, English language abstracts of each of those patents have been provided herewith.

No fee is believed to be required in connection with the filing of this Information Disclosure Statement because it is being submitted within three months of the filing of the above-captioned application.

Applicants believe that their APPARATUS FOR ETCHING SEMICONDUCTOR SAMPLES AND A SOURCE FOR PROVIDING A GAS BY SUBLIMATION THERETO as described and claimed in the present application is neither taught nor suggested by this prior art. Accordingly, applicants' invention is believed to be patentable over these prior art references.

Respectfully submitted,

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A handwritten signature in black ink, appearing to read "Philip E. Levy".

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